

# ABSTRACT

There is provided a laminated resist which is transparent in the case of exposure light of not less than 193 nm and can form a fine pattern having an intended form without defects with good reproducibility. The laminated resist has a photoresist layer (L1) and a transparent protective layer (L2) on a substrate and the protective layer (L2) is formed on an outermost surface of the laminated resist. The protective layer (L2) has an absorption coefficient of not more than  $1.0 \mu\text{m}^{-1}$  in the case of ultraviolet light of a wavelength of not less than 193 nm, a dissolution rate in a developing solution of not less than 50 nm/sec and a dissolution rate in pure water of not more than 10 nm/min.